REMARKS

Applicants thank the Examiner for the courtesy extended to Applicants' attorney during the interview held May 13, 2004, in the above-identified application. During the interview, Applicants' attorney discussed the issues raised in the Office Action, and explained why the rejected claim complies with 35 U.S.C. § 112, second paragraph. The discussion is summarized and expanded upon below.

The rejection of Claim 21 under 35 U.S.C. § 112, second paragraph, is respectfully traversed. Claim 21 is set forth below:

The method according to Claim 20, wherein the film material is discharged onto the surface of the drum, which is plated with chromium, to thereby form the polyvinyl alcohol film.

The Examiner finds that it is not clear "how the use of a chromium plated drum materially manipulates the process." (Emphasis added.)

In reply, and as discussed during the above-referenced interview, there is no requirement in a dependent process claim that a recited limitation "materially manipulate" the process. Indeed, a dependent claim is proper so long as it places **any** limitation on the claim from which it depends. The specification at page 9, first paragraph, describes that the use of, for example, a chromium layer on the drum, provides enhanced endurance to the drum. There is no reason in law or policy why this advantageous feature cannot be the subject of a dependent claim.

For all the above reasons, it is respectfully requested that the rejection be withdrawn.

Applicants gratefully acknowledge the Examiner's allowance of Claims 20 and 22-24.

Nevertheless, Applicants' respectfully submit that all of the presently-pending claims in this

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application are in condition for allowance. Accordingly, the Examiner is respectfully requested to pass this application to issue.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,

MAIER & NEUSTADT, P.C.

Norman F. Oblon

Harris A. Pitlick

Registration No. 38,779

Customer Number 22850

Tel: (703) 413-3000 Fax: (703) 413 -2220 (OSMMN 08/03) NFO/HAP/cja